L	Hits	Search Text	DB	Time stamp
Number				
1	0	(HSG or (hemispheric adj grain)) same (phase with change)	USPAT; US-PGPUB	2004/05/01 09:15
2	103	(HSG or (hemispheric adj grain)) same	USPAT;	2004/05/01
		(phase)	US-PGPUB	10:05
3	91	((HSG or (hemispheric adj grain)) same (phase)) and @ad<20011231	USPAT; US-PGPUB	2004/05/01 10:15
4	9	(HSG or (hemispheric adj grain)) same	EPO; JPO;	2004/05/01
		(phase)	DERWENT;	09:24
	, ,	(#C200075#) PX	IBM_TDB	2004/05/01
5	1	("6309975").PN.	USPAT; US-PGPUB	2004/05/01 09:38
6	1	(HSG or (hemispheric adj grain)) same	USPAT;	2004/05/01
	, '	(chalcogenide)	US-PGPUB	13:12   2004/05/01
7	1	(HSG or (hemispheric adj grain)) same (chalcogenide or "GeSbTe" or "TeGeSb")	USPAT; US-PGPUB	10:06
8	11	(HSG or (hemispheric adj grain)) and	USPAT;	2004/05/01
	222	(chalcogenide or "GeSbTe" or "TeGeSb")	US-PGPUB	10:15
9	333	(phase with change) same adhesion	USPAT; US-PGPUB	2004/05/01 10:16
10	276	((phase with change) same adhesion) and	USPAT;	2004/05/01
11	,,,	(ad<20011231	US-PGPUB	13:14
11	258	(phase near3 change) same adhesion	USPAT; US-PGPUB	10:16
12	211	((phase near3 change) same adhesion) and	USPAT;	2004/05/01
12	1.55	(MSC on (homisphonis add grain)) same	US-PGPUB	10:16
13	467	(HSG or (hemispheric adj grain)) same ((programmable) or (phase adj changeable)	USPAT; US-PGPUB	13:20
		or (recordable) or (recording) or		
	211	(memory))	MCDAM.	2004/05/01
14	211	(HSG or (hemispheric adj grain)) with ((programmable) or (phase adj changeable)	USPAT; US-PGPUB	13:14
		or (recordable) or (recording) or		
1.5	170	(memory))	USPAT;	2004/05/01
15	170	((HSG or (hemispheric adj grain)) with ((programmable) or (phase adj changeable)	US-PGPUB	13:23
		or (recordable) or (recording) or		
16	18849	(memory))) and @ad<20011231 (recording or (phase adj (change or	USPAT;	2004/05/01
10	10043	changeable))) with (adhesion or adhesive	US-PGPUB	13:22
		or interface or interfacial)		2004/05/01
17	16164	(recording or (phase adj (change or changeable))) with (adhesive or interface	USPAT; US-PGPUB	2004/05/01
		or interfacial)		
18	4374		USPAT;	2004/05/01
19	139	changeable))) with (adhesive) (phase adj (change or changeable)) with	US-PGPUB USPAT;	13:22 2004/05/01
		(adhesive)	US-PGPUB	13:50
20	101	((phase adj (change or changeable)) with	USPAT; US-PGPUB	2004/05/01 13:50
21	3	(adhesive)) and @ad<20011231 (((phase adj (change or changeable)) with	US-PGPUB USPAT;	2004/05/01
		(adhesive)) and @ad<20011231) and	US-PGPUB	13:25
22	0	(adhesive with (silicon or HSG))	IISDAT.	2004/05/01
22		(((phase adj (change or changeable)) with (adhesive)) and @ad<20011231) and	USPAT; US-PGPUB	13:25
		(adhesive with (hemispheric))		
23	0	(((phase adj (change or changeable)) with (adhesive)) and @ad<20011231) and	USPAT; US-PGPUB	2004/05/01
		(adhesive with (hemispherical))	US-FGFUB	13.23
24	50	(phase adj (change or changeable)) with	EPO; JPO;	2004/05/01
		(adhesive)	DERWENT; IBM TDB	13:25
25	2	((phase adj (change or changeable)) with	EPO; JPO;	2004/05/01
		(adhesive)) and (adhesive with (silicon	DERWENT;	13:26
26	52	or HSG)) (phase adj (change or changeable)) with	IBM_TDB USPAT;	2004/05/01
1	32	(interfacial)	US-PGPUB	13:54
27	28	((phase adj (change or changeable)) with	USPAT;	2004/05/01
L	L	(interfacial)) and @ad<20011231	US-PGPUB	13:50

28	7 (phase adj (change or changeable)) with	EPO; JPO;	2004/05/01
	(interfacial)	DERWENT;	13:55
		IBM TDB	

US-PAT-NO:

6566700

DOCUMENT-IDENTIFIER:

US 6566700 B2

TITLE:

Carbon-containing interfacial layer

for phase-change

memory

----- KWIC -----

Abstract Text - ABTX (1):

A <u>phase-change</u> memory cell may be formed with a carbon-containing

interfacial layer that heats a phase-change material. By
forming the

phase-change material in contact, in one embodiment, with
the carbon containing

interfacial layer, the amount of heat that may be applied
to the phase-change

material, at a given current and temperature, may be increased. In some

embodiments, the performance of the interfacial layer at high temperatures may

be improved by using a wide band gap semiconductor material such as silicon carbide.

Application Filing Date - AD (1): 20011011

TITLE - TI (1):

Carbon-containing <u>interfacial</u> layer for <u>phase-change</u> memory

Detailed Description Text - DETX (4):

A carbon-containing <u>interfacial</u> layer 20 may be positioned between the

phase-change material layer 24 and the insulator 16. In
one embodiment, a

cylindrical sidewall spacer 22 may be defined within a tubular pore that is

covered by the carbon-containing <u>int rfacial</u> layer 20 and the <u>phas -change</u> material layer 24.

Detailed Description Text - DETX (10):

In some embodiments of the present invention, a layer (not shown) may be provided to improve the adhesion between the **phase-change** material layer 24 and the carbon-containing **interfacial** layer 20. Suitable adhesion promoting layers may include any conductive materials including titanium, titanium nitride and Tungsten, as a few examples.

Detailed Description Text - DETX (15):

Through the use of a carbon-containing <u>interfacial</u> layer 20, the resistivity

of the phase-change material heater may be substantially increased while at the

same time improving the heating performance of the heater at high temperatures.

The heater effectively includes the series combination of the lower electrode

14 and the carbon-containing interfacial layer 20.

However, a series resistive

combination is dominated by the element with the higher resistance, which may

be the carbon-containing interfacial layer 20 in some embodiments. As a

result, the resistance of the series combination of layers 20 and 14 may be

dominated by the resistance of the interfacial layer 20.

## Claims Text - CLTX (5):

5. The memory of claim 4 wherein said phase-change
material is formed on
said carbon-containing interfacial
layer and in said pore.

## Claims Text - CLTX (7):

7. The memory of claim 6 wherein said sidewall spacer is positioned between said interfacial layer and said phase-change material.

Claims Text - CLTX (9):

9. An electronic device comprising: digital signal processor; and a memory coupled to said processor, said memory including a surface, a silicon carbide interfacial layer over said surface and a phase-change material over said silicon carbide layer.